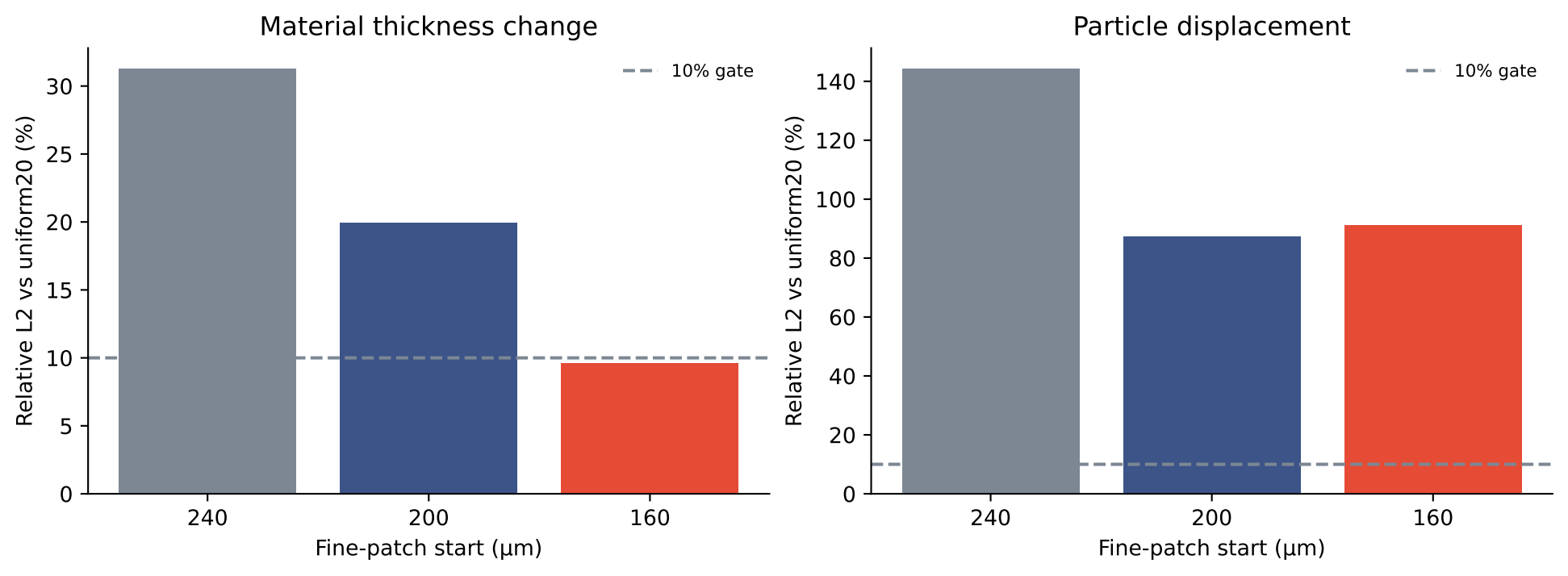

Material thickness change
Relative L2 vs uniform20 (%)
10% gate
0
5
10
15
20
25
30
240
200
160
Fine-patch start (μm)
Particle displacement
Relative L2 vs uniform20 (%)
10% gate
0
20
40
60
80
100
120
140
240
200
160
Fine-patch start (μm)